

Field-averaging micro lenses that synthesize highly uniform illumination in coherent EUV optical systems

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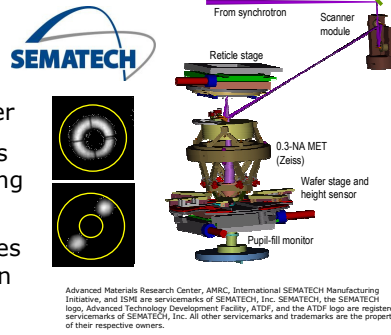


MOTIVATION

- Illumination uniformity and reproducibility in EUV microfield exposure tools is critical to many aspects of the EUV lithography development task.
- To address this concern, field-integrating fly's eye elements are often used in illuminator designs.

SEMATECH BERKELEY MET

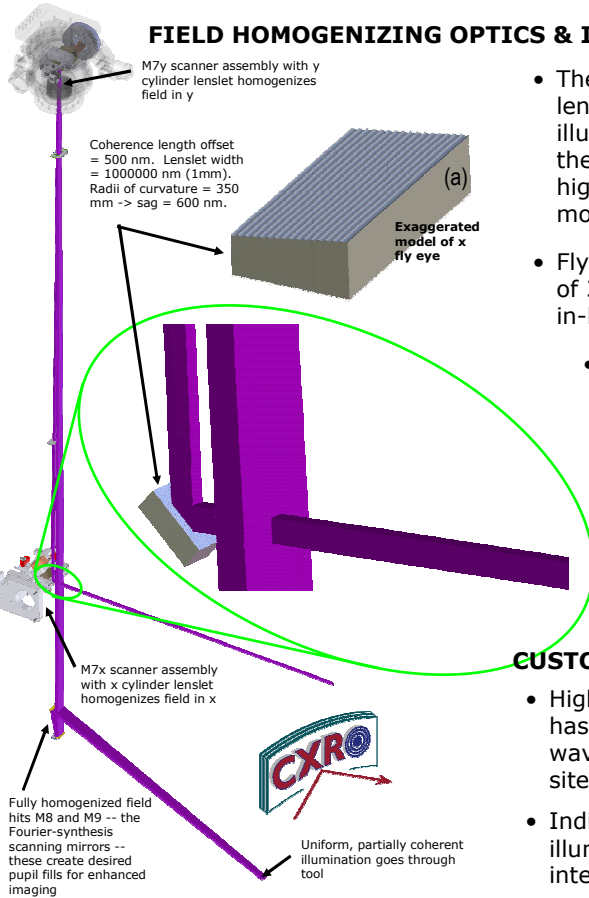
- 0.3 NA Zeiss optic in 5x reduction configuration
- 600x200 μm field size at wafer
- Support for arbitrary pupil fills with Fourier-synthesis scanning illuminator
- Ultrahigh resolution capabilities from a conventional projection EUV system



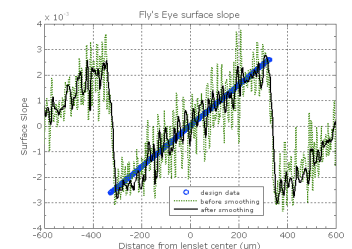
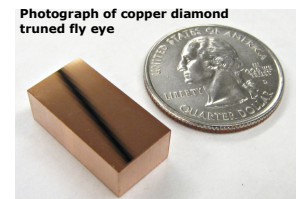
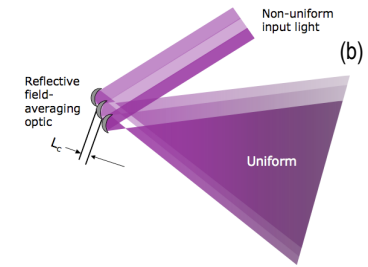
GOALS

- Expand uniformly illuminated field size to match capabilities of MET projection optics (3-mm x 1-mm at mask)
- Enable programmable field size
- Maintain system throughput
- Maintain programmable coherence (pupil fill) functionality of the system

FIELD HOMOGENIZING OPTICS & IMPLEMENTATION AT EUV



- The field-homogenizing optic is an array of small lenslets that map sub-sections of an incoming illumination footprint to an overlap region wherein the expanded sub-fields are averaged to produce a highly uniform footprint. It is shown in reflection mode to the right.
- Fly's Eyes are designed to fill 1-mm x 1-mm subset of 3-mm x 1-mm field. Programmable scanners and in-house software create desired field fill patterns
- Small NA of homogenizing optics does not affect our ability to controllably de-coherenize the illumination and achieve desired pupil fills
- We've decoupled the Fly's Eye stage into a pair of orthogonal cylindrical lenslet arrays. At least five lenslets intercept the incoming illumination footprint in each imaging direction, mapping the uniform fill to the surfaces of the existing x and y Fourier-synthesis scanning mirrors.

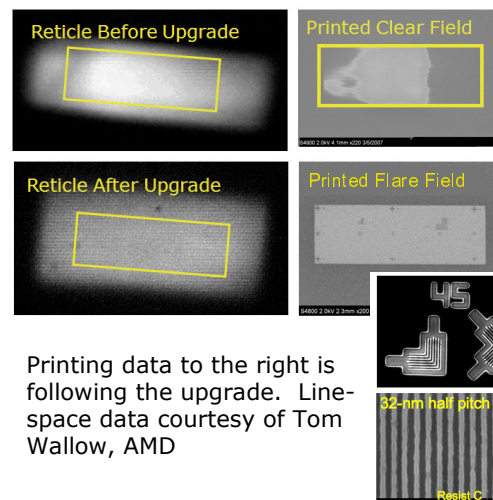


CUSTOM FLY'S EYE'S FOR COHERENT EUV

- High spatial coherence of synchrotron radiation has potential to cause interference between wavefronts emerging from different lenslet sites in Fly's Eye array
- Individual lenslets are offset by the 500-nm illumination coherence length to eliminate interference [see (a) and (b)].

- In house smoothing renders diamond-turned surfaces suitable for multilayer deposition (see OP-P06).
- Diamond-turned optics by NU-TEK Precision Optical Corp in Aberdeen MD.

POST-UPGRADE SYSTEM PERFORMANCE



Printing data to the right is following the upgrade. Line-space data courtesy of Tom Wallow, AMD

- Before and after pictures of reticle field and printed clear fields show improved performance.
- Lithographically measured uniformity = 6.5% peak-to-valley across 9 points spanning the field

CONCLUSIONS

- We've developed a field-averaging scanning-Fly's Eye stage enabling non-uniform, high-coherence sources to be used in applications requiring high illumination uniformity
- The system has been successfully integrated into the existing illuminator of the SEMATECH Berkeley MET and we report post-upgrade intensity uniformity across the 200x600 μm wafer-side field of view of 6.5%.

ACKNOWLEDGEMENTS

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